WO 2005/091075 PCT/NL2005/000211

- 15 -

CLAIMS

- 1. Method for producing a base material (25) for screen
 5 printing, which comprises a screen (5), a resist layer (13)
 comprising photosensitive material and a protective film
 (10), the method comprising the steps of:
 - a) applying a first resist layer (15) to one side of the protective film (10),
- 10 b) drying the first resist layer (15),

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- c) applying an additional resist layer (17) to the first resist layer (15), and
- d) then applying a screen (5) to the additional resist layer (17), the side of the additional resist layer (17) to which the screen (5) is applied being wet, and the screen (5) being pressed into the additional resist layer (17) under pressure from a pressure-exerting element which makes direct contact with the screen (5), in particular a roller (1),
- and in which the resist layer (13) comprises the additional resist layer (17) and the first resist layer (15).
 - 2. Method according to claim 1, in which the screen (5) is applied without the additional resist layer (17) being dried beforehand.
 - 3. Method according to one of the preceding claims, in which the screen (5) which is applied is an electroformed screen.
- 30 4. Method according to claim 1, in which the pressure-exerting surface of the roller (1) is provided with a coating material with an open-cell structure.
- 5. Method according to one of the preceding claims, in which
 the roller (1) makes direct contact with the screen (5) in
 the tangential direction over a length which is less than
 the diameter of the openings of the screen (5) at the
 contact surface of the screen.

- 6. Method according to one of the preceding claims, in which the roller (1) is compressible.
- 5 7. Method according to one of the preceding claims, in which the first resist layer (15) which is applied has a thickness at least equal to that of the additional resist layer (17) which is applied.
- 10 8. Method according to one of the preceding claims, in which the additional resist layer (17) which is applied is from 2 to 10 micrometres thick.
- 9. Method according to one of the preceding claims, in which
 the additional resist layer (17) which is applied comprises
 the same type of resist as the first resist layer (15)
 which is applied.
- 10. Method according to one of the preceding claims, in which
 20 two intermediate steps are carried out between steps b) and
 c), namely:

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- i) covering the first resist layer (15) with a separating sheet and rolling up the subassembly comprising protective film (10), first resist layer (15) and separating sheet, and
- ii) then unrolling the rolled-up subassembly and removing the separating sheet.
- 11. Base material (25) for screen printing, which comprises a

 screen (5), a resist layer (13) comprising photosensitive
 material and a protective film (10), the screen (5)
 comprising a network of dykes which delimit openings,
 characterized in that the surface of the resist layer (13),
 on the side on which protective film (10) is present, is

 sufficiently smooth for the Rz value of the said surface to
 be lower than 15 micrometres.
 - 12. Base material (25) for screen printing according to

WO 2005/091075 PCT/NL2005/000211

- 17 -

claim 11, characterized in that the distance (d) from the dykes (6) of the screen (5) to the surface of the resist layer (13) on the side of the protective film (10) is uniform.

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13. Base material (25) for screen printing according to claim 11 or 12, characterized in that the height (h) of the resist layer (13) is uniform between the dykes (6) of the screen (5).

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14. Base material (25) for screen printing, which comprises an electroformed screen (5), a resist layer (13) of photosensitive material and a protective film (10), in particular according to claim 11, 12 or 13.

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